

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re patent application of

David Abraham et al.

Serial No.: 10/680,260

Group Art Unit: Not Yet Assigned

Filing Date: October 8, 2003

Examiner: Unknown

For: METHOD AND SYSTEM FOR PATTERNING OF MAGNETIC THIN FILMS
USING GASEOUS TRANSFORMATION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT


Sir:

Under the provisions of 37 CFR §1.97 through §1.99 and pursuant to applicant's duty of disclosure under 37 CFR §1.56, applicant respectfully brings the following documents listed on the attached form PTO-1449, to the attention of the Examiner in charge of the above-identified application. Copies of the listed documents are provided herewith for the convenience of the Examiner. In compliance with the concise explanation requirement under 37 CFR §1.98(a)(3), the relevance of three of these documents is discussed on page 2 of the subject application. This citation does not constitute an admission that the references are relevant or material to the claims. They are only cited as constituting related art of which the applicant is aware.

It is respectfully requested that the listed references be considered by the Examiner and formally made of record in this application.

Please charge any deficiencies in fees and credit any overpayment of fees to Assignee's Deposit Account No. 50-0510.

Respectfully submitted,



Sean M. McGinn

Registration No. 34,386

Date: 1/8/04

McGinn & Gibb, PLLC

Intellectual Property Law

8321 Old Courthouse Road, Suite 200

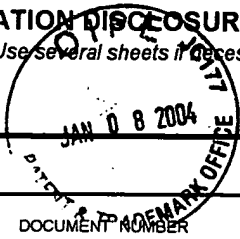
Vienna, VA 22182-3817

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INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)



ATTY DOCKET NO.

YOR920030013US1

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APPLICANT(S)

David Abraham et al.

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U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	6,440,520	08/27/02	Baglin et al.			
	6,331,364	12/18/01	Baglin et al.			
	6,383,597	05/07/02	Fullerton et al.			

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

		Bruenger et al., "Ion projection lithography for resistless patterning of thin magnetic films", 25th International Conference on Micro and Nano Engineering, Rome Italy, 21-23 September 1999 and Microelectron. Eng. (Netherlands), Vol. 53, No. 1-4, June 2000, Pages 605-608.
		Eugene Chen, et al., "Magnetic tunnel junction pattern technique", Silicon Magnetic Systems, Cypress Semiconductor, San Jose, CA, Journal of Applies Physics, Volume 93, Number 10, May 15, 2003, p. 8379.

EXAMINER

DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE CITATION*(Use several sheets if necessary)*

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OTPA JAN. 08 2004 PATENT & TRADEMARK OFFICE						

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	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

OTHER DOCUMENTS *(Including Author, Title, Date, Pertinent Pages, Etc.)*

		B.D. Terris et al., "Patterning magnetic films by ion beam irradiation", J. Appl. Phys., (USA), Vol. 87, No. 9, Pt. 1-3, May 1, 2000, pp.7004-6.
		Corporate Associates, "Physics Helps Redesign Dow Chemical," 39 The Industrial Physicist, April 1999, American Institute of Physics, page 1.

EXAMINER

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